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J.C. PATENTS

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CERTIFICATE OF TRANSMISSION

April 19, 2007

AMENDMENT AFTER ALLOWANCE

Atty Docket No.	:	JCLA7109-R
Appl. No.	:	10/603,924
Filing Date	:	June, 24, 2003
Pages	:	Cover + 12

BY FACSIMILE ONLY

Fax No.	:	571-273-8300
Attention	:	EXAMINER: NGUYEN, THANH T.
Group Unit	:	2813
From	:	Jiawei Huang, Reg. No. 43,330
MESSAGE	:	Enclosed herewith is a Amendment After Allowance with amended drawings in 12 pages.

Sir:

I hereby certify that this correspondence is being facsimile transmitted to the Patent and Trademark Office on April 19, 2007 at the above indicated fax number.

Sign by:

Michelle Chang

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APR 1 9 2007

Application No.: 10/603,924 Docket No.: JCLA7109-R

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Ap	plica	tion of:)			
THANH	т	Hu et al.)	Examiner	:	NGUYEN,
Serial No		10/603,924)	Art Unit	:	2813
Filed	: .	June 24, 2003)	Docket No.	:	JCLA7109-R
For	:	METHOD OF REMOVING CONTAMINANTS FROM A SILICON WAFER AFTER CHEMICAL-MECHAMICAL POLISHING OPERATION))))			

AMENDMENTS AFTER ALLOWANCE UNDER 37 CFR 1.312

MAIL STOP AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir,

The Notice of Allowance dated January 24, 2007 has been carefully considered. In response thereto, please enter the following amendments and consider the remarks hereinafter.